



# **B-based ML coatings for Blue-X**



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IOF





#### History

- **1997:** Start of EUV multilayer development @ Fraunhofer IOF
- **2013:** August 1<sup>st</sup>: Operations start @ optiX fab.
- **TODAY:** Delivery of **14,258 EUV and X-ray mirrors** to customers
- Mission Fabrication of customized EUV optics and optical components for EUV lithography @ 13.5 nm, for EUV, soft and hard X-ray applications, synchrotron and FEL beamlines, metrology, R&D, HHG sources, etc.



Torsten Feigl



Marco Perske



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**Tobias Fiedler** 



Philipp Naujok

2 I 2018 International Workshop on EUV and Soft X-ray Sources, Prague, Nov. 6, 2018



## **ML coatings for short wavelengths**

main issues for ML coatings at shorter wavelengths ( $\lambda < 13.5$  nm):



#### **1**<sup>st</sup>: lower reflectance

typical experimental values for near normal incidence:

13.5 nm: R ≤ 70 %

6.7 nm: R ≤ 65 %

4.4 nm: R ≤ 15 %

2.4 nm: R ≤ 20 %

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2<sup>nd</sup>: lower bandwidth



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## **ML coatings for short wavelengths**

- strongly decreasing bandwidth (FWHM) of the ML coating for shorter wavelengths
- reason: higher number of required contributing interfaces



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λ, nm	1.4	2.4	2.7	4.4	6.7	9.0	12.0	13.5
R, %	0.02	18.1	26.2	16.8	61.0	36.0	49.2	70.1
FWHM, nm	0.002	0.005	0.008	0.02	0.05	0.11	0.32	0.52



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# $La/B_4C$ – simulation vs. experiment

#### Simulation:

- > 250 bilayers of La and B<sub>4</sub>C
- period thickness (La + B<sub>4</sub>C): d = 3.4 nm
- ideal layers:



#### First experiments:

- very low reflectance
- huge difference between simulation and experiment





# $La/B_4C$ – simulation vs. experiment

#### Simulation:

- > 250 bilayers of La and B<sub>4</sub>C
- period thickness (La + B<sub>4</sub>C): d = 3.4 nm
- ideal layers:

#### **Optimized experiments:**

- still low reflectance
- huge difference between simulation and experiment







## HR-TEM of La/B<sub>4</sub>C-ML



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## **Reducing the interface width**

1. Utilizing chemically stable materials







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1. Utilizing chemically stable materials





2. Application of barrier layers

B <sub>4</sub> C
La
B <sub>4</sub> C
La
B <sub>4</sub> C
La
B <sub>4</sub> C
La (~ 1.4 nm)
B <sub>4</sub> C (~ 2.0 nm)
substrate





Theory:

- Iowering chemical reactivity between B and La
- high peak reflectance achievable using La compounds
- expectation: higher experimental reflectance due to more narrow interfaces
- promising candidates:
  - LaN [1]
  - LaC<sub>2</sub>



[1] T. Tsarfati et al., Thin Solid Films 518, 1365–1368 (2009)







	EUVR @ 6,65 nm				
System	R <sub>exp</sub> [%]	Δλ <sub>exp</sub> [nm]			
La/B <sub>4</sub> C	51.1	0.036			

P. Naujok et al., Thin Solid Films 612, 414-418, 2016







- increased reflectance due to less chemical rection between La and B<sub>4</sub>C
  - R = 55,2 % @ 6,65 nm (LaC<sub>2</sub>)

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- increased reflectance due to less chemical rection between La and B<sub>4</sub>C
  - R = 55,2 % @ 6,65 nm (LaC<sub>2</sub>)
  - R = 58,1 % @ 6,65 nm (LaN)

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## **Reducing the interface width**







- barrier thickness 0.3 ... 0.5 nm
- important critera:
  - optical properties
  - film growth
  - chemical reactivity with La, B, C, N

#### simulation for ideal layers:















- huge impact on reflectance by extremly thin barriers
- no increased reflectane with

Mo (ΔR = - 15.3 %) ZrN (ΔR = - 8.0 %)





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 increased reflectance with C-barriers

C (ΔR = + 2.0 %)

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- $LaN/B_4C$ : R = 58.1 %





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#### next steps:

- current championship data: R = 64.1 % using La/LaN/B [2]
- target for HVM: R > 70 %
- therefore: lower chemical reactivity, optimize barrier layers needed

[2] D. Kuznetsov et al., Optics Letters 40 (16) (2015)





# Thank you.